

DUAL DAMASCENE INTERCONNECT STRUCTURE USING LOW STRESS
FLUOROSILICATE INSULATOR WITH COPPER CONDUCTORS

Abstract of the Disclosure

- 5 A metallization insulating structure, having
a substrate;
a substantially fluorine free insulating layer formed on the
substrate, having a height, h_i ;
a fluorine containing insulating layer formed on the
10 substantially fluorine free insulating layer, having a
height h_f .